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Form PTO 1449 (Rev. 2-32) U.S. Department of Commerce Patent and Trademark Office				Atty. Docket No. LMPY-9220	Serial No.: 09/771,366		
Information Disclosure Statement by Applicant				Applicant: Dirk Basting, et al.			
(Use several sheets if necessary)				Filed: January 15, 2001 Group: <u>2881-2828</u>			
U.S. Patent Documents							
Init.		Document No.	Date	Name	Class	Subclass	Filing Date
<u>83</u>		3,471,800	10/07/69	Congleton, et al.	331	94.5	12/17/64
<u>1</u>		3,546,622	12/08/70	Peterson, et al.	331	94.5	10/29/65
		3,609,586	09/28/71	Danielmeyer	331	94.5	06/18/69
		3,611,436	10/05/71	Rigrod	331	94.5	01/24/69
		3,775,699	11/27/73	Cassels	331	94.5	02/03/71
		3,806,829	04/23/74	Duston, et al.	331	94.5	04/13/71
		3,868,592	02/25/75	Yarborough, et al.	331	94.5	05/30/73
		4,016,504	04/05/77	Klauminzer	331	94.5	04/12/76
		4,229,710	10/21/80	Shoshan	331	94.5	07/03/78
		4,319,843	03/16/82	Gornall	356	346	02/25/80
		4,393,505	07/12/83	Fahlen	372	57	11/03/81
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		4,611,270	09/09/86	Klauminzer, et al.	364	183	09/16/83
		4,616,908	10/14/86	King	350	576	07/19/84
		4,691,322	09/01/87	Nozue, et al.	372	82	01/22/86
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		4,905,243	02/27/90	Lokai, et al.	372	32	12/22/88
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		4,942,583	07/17/90	Nazarathy, et al.	372	20	06/17/88
		4,972,429	11/20/90	Herbst	372	100	11/18/88
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		4,977,563	12/11/90	Nakatani, et al.	372	32	09/22/88
<u>DS</u>		4,985,898	01/15/91	Furuya, et al.	372	106	03/01/90
Examiner <u>JEPPESEN Boston</u>				Date Considered <u>9/4/2003</u>			
Examiner: Initial if citation considered, whether or not citation is in conference with MPEP 609; Draw line through citation if not conformance and not considered. Include a copy of this form with the next communication to applicant.							



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<u>J3</u>		5,025,445	07/18/91	Anderson, et al.	372	20	11/22/90
		5,051,558	09/24/91	Sukhman	219	121.68	03/20/89
		5,081,635	01/14/92	Wakabayashi, et al.	372	57	02/26/90
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		5,142,543	08/25/92	Wakabayashi, et al.	372	32	01/27/89
		5,150,370	09/22/92	Furuya, et al.	372	106	12/12/90
		5,161,238	11/03/92	Mehmke	359	738	03/31/89
		5,198,872	03/30/93	Wakabayashi, et al.	356	352	05/18/90
		5,218,421	06/08/93	Wakabayashi, et al.	356	352	02/15/91
		5,221,823	06/22/93	Usui	219	121.78	01/17/92
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		5,596,596	01/21/97	Wakabayashi, et al.	372	102	12/15/95
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<u>83</u>		5,646,954	07/08/97	Das, et al.	372	55	02/12/96
<u>83</u>		5,657,334	08/12/97	Das, et al.	372	33	02/15/96
<u>83</u>		5,659,419	08/19/97	Lokai, et al.	359	330	07/11/95
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		5,763,855	06/09/98	Shioji	219	121.84	06/02/95
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		5,811,753	09/22/98	Weick, et al.	219	121.78	06/19/96
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		5,970,082	10/19/99	Ershov	372	102	07/01/97
<u>83</u>		5,978,346	11/02/99	Mizuno, et al.	369	112	01/30/98
<u>83</u>		5,978,391	11/02/99	Das, et al.	372	20	07/18/97
<u>83</u>		5,978,394	11/02/99	Newman, et al.	372	32	10/02/98
Examiner	<u>JEPSON ZAMN</u>			Date Considered <u>9/4/2003</u>			

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<u>J3</u>		5,978,406	11/02/99	Rokni, et al.	372	58	01/30/98	
<u>J3</u>		5,978,409	11/02/99	Das, et al.	372	100	09/28/98	
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		6,028,872	06/22/00	Partlo, et al.	372	38	12/15/98	
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		6,078,599	06/20/00	Everage, et al.	372	20	07/12/97	
		6,094,448	07/25/00	Fomenkov, et al.	372	102	02/11/99	
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		6,240,110	05/29/01	Ershov	372	20	09/27/99	
<u>J3</u>		6,327,290	12/04/01	Govorkov, et al.	372	61	06/14/00	
<u>J3</u>		6,345,065	02/05/02	Kleinschmidt, et al.	372	57	05/24/99	
Foreign Documents								
Translation								
Init.		Document No.	Date	Country	Class	Subclass	Yes	No
<u>J3</u>		44-8147	1969	Japan	100	D0		X
<u>J3</u>		60-205420	10/17/85	Japan	G02B	27/00	Abstract	
<u>J3</u>		8-274399	11/18/86	Japan	H04S	3/104	X	
<u>J3</u>		61-139950	06/1986	Japan				
<u>J3</u>		62-160783	07/16/87	Japan	H01S	3/115	X	
Examiner	<i>JEP not BAST</i>				Date Considered <u>7/14/03</u>			
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Filed: January 15, 2001 Group: 281 2828**Foreign Documents****Translation**

Init.	Document No.	Date	Country	Class	Subclass	Yes	No
	10-209533	1998	Japan	H01S	3/08		X
	63-45875	1988	Japan	H01S	3/08		X
	1-179477	1989	Japan	H01S	3/08		X
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	3-82183	1991	Japan	H01S	3/08		X
	EP 0 472 727 A1	03/04/92	EPO	H01S	3/1055	X	
	EP 0 395 717 B1	09/1993	EPO	A61B	17/36	X	
	JP 5-291674	11/05/93	Japan	H01S	3/1055	X	
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	WO 98/57213	12/17/98	PCT	G02B	27/00		X
	WO 98/59364	12/30/98	PCT	H01L	21/027		X
	EP 0 955706 A1	01/27/99	EPA	H01S	3/08	X	
	WO 99/04467	01/28/99	PCT	H01S	3/134	X	
	WO 99/08133	02/18/99	PCT	G03B	27/42	X	
	WO 99/19952	04/23/99	PCT	H01S	3/22	X	
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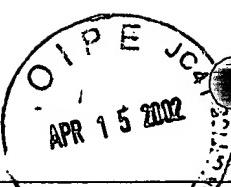
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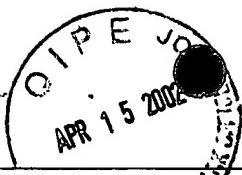
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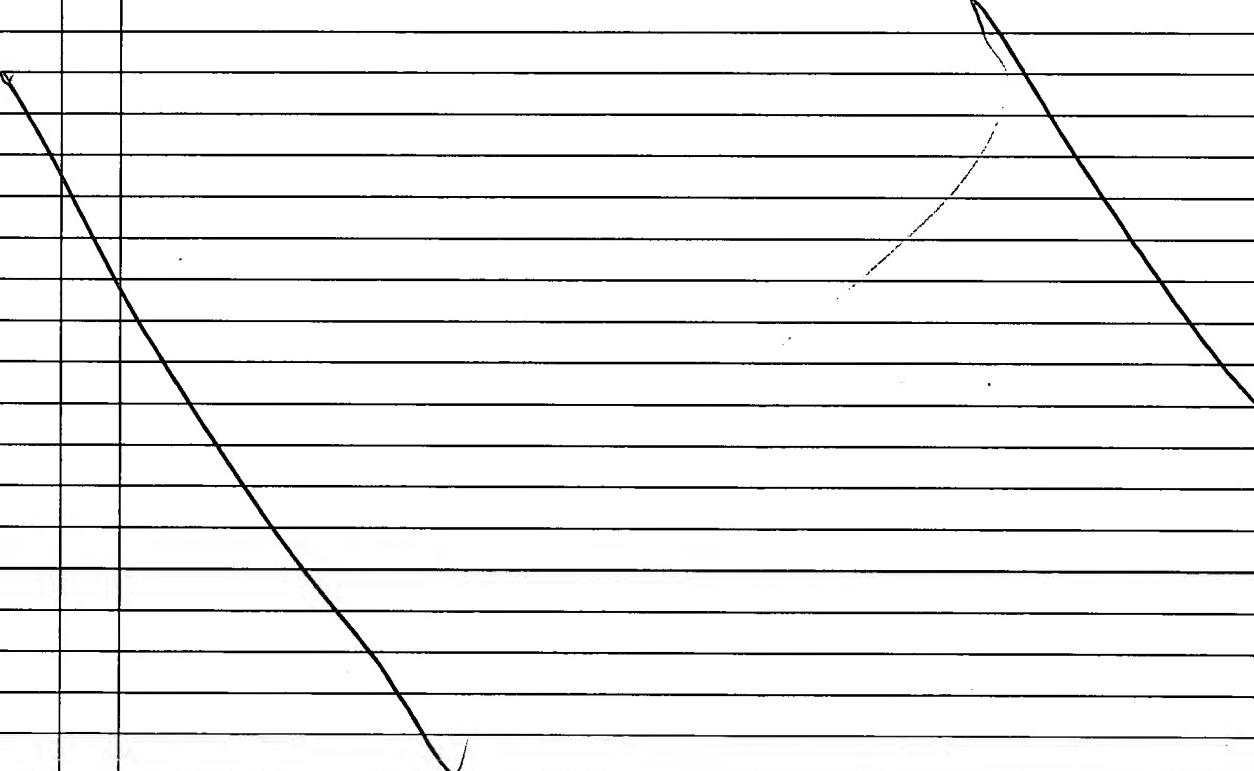


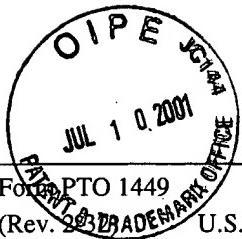
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